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APPLICATION NO.
09/863,338

**SECOND INFORMATION DISCLOSURE
STATEMENT BY SIGNIFICANT**

FILING DATE
May 24, 2001

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MAIL DATE CANCELLED

PATENT & TRADEMARK OFFICE

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FOREIGN PATENT DOCUMENTS					
Examiner Initials	Document Number	Kind Code (if known)	Country	Date of Publication (MM-DD-YYYY)	Translation Yes No
du	7-201749		Japan	08-04-1995	<input checked="" type="checkbox"/> <input type="checkbox"/>
du	2837087		Japan	10-09-1998	<input checked="" type="checkbox"/> <input type="checkbox"/>

NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
sm	Robert C. REID et al. "Lennard-Jones Potentials as Determined from Viscosity Data (Appendix B)", <i>The Properties of Gases and Liquids</i> , McGraw-Hill, Inc., Copyright 1987, p.734, Index
sm	R. Byron BIRD et al. "Diffusivity and the Mechanisms of Mass Transport; Theory of Ordinary Diffusion in Gases at Low Density", <i>Transport Phenomena</i> , John Wiley & Sons, Inc., Copyright 1960, p. 508-513
sm	"Flow of Atoms and Molecules—Rarefied Gas Dynamics and its Applications", section 2.6.4, The Japan Society of Mechanical Engineers, 1996, Kyoritsu Shuppan Co., Ltd.
sm	Shingo KADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation
sm	Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON Si", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995
sm	Riccardo d'AGOSTINO et al., "PLASMA ETCHING OF Si and SiO ₂ in SF ₆ -O ₂ MIXTURES", J. Appl. Phys. 52(1), January 1981, pp. 162-167

Examiner Signature	<i>[Signature]</i>	Date Considered	9/25/03
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EXAMINER: Initial reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. **SEND TO:** Assistant Commissioner for Patents, Washington, DC 20231.

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